

ABSTRACT

[0048] The present invention relates to an immersion lithographic system for patterning a
5 work piece arranged at an image plane and covered at least partly with a layer sensitive to
electromagnetic radiation. Said system comprising a source emitting electromagnetic
radiation onto an object plane, a mask, adapted to receive and modulate said electromagnetic
radiation at said object plane and to relay said electromagnetic radiation toward said work
piece, and an immersion medium contacting at least a portion of a final lens of said
10 lithographic system and a portion of said work piece, wherein an area of said contacting is
restricted by capillary forces. The invention further relates to a method for patterning a
workpiece.